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| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO | |
|---------------------|---------------|----------------------|---------------------|------------------|--|
| 09/667,706 | 09/22/2000 | Ken Inoue | NEC00P267-hk | 9955 | |
| 75 | 90 01/17/2002 | | | | |
| McGinn & Gibb, PLLC | | | EXAMINER | | |
| SUITE 200 | JRTHOUSE RD. | | OWENS, DO | OWENS, DOUGLAS W | |
| VIENNA, VA | 22182 | | ART UNIT | PAPER NUMBER | |
| | | | 2811 | | |

DATE MAILED: 01/17/2002

Please find below and/or attached an Office communication concerning this application or proceeding.

| | Application No. | | φplicant(s) | · | | | | |
|--|--|---|---|-----------------------|--|--|--|--|
| Office Action Summer | 09/667,706 | | INOUE ET AL. | | | | | |
| . Office Action Summary | Examiner | | Art Unit | | | | | |
| TI MAIL DIO DATE JAL' | Douglas W Ower | | 2811 | Idross | | | | |
| The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply | | | | | | | | |
| A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period was Failure to reply within the set or extended period for reply will, by statute, - Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b). | ele(a). In no event, howen within the statutory min ill apply and will expire cause the application to | ver, may a reply be tin imum of thirty (30) day: SIX (6) MONTHS from become ABANDONE | nely filed s will be considered time the mailing date of this of D (35 U.S.C. § 133). | ly. communication. | | | | |
| Status | ocombar 2001 | | | | | | | |
| 1) Responsive to communication(s) filed on 19 E | | nal | | | | | | |
| 2a) ☐ This action is FINAL. 2b) ☐ This action is non-final. 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213. | | | | | | | | |
| Disposition of Claims | | , | | | | | | |
| 4)⊠ Claim(s) <u>1-14</u> is/are pending in the application. | | | | | | | | |
| 4a) Of the above claim(s) <u>1-4,10 and 11</u> is/are v | withdrawn from c | onsideration. | | | | | | |
| 5) Claim(s) is/are allowed. | | | | | | | | |
| 6)⊠ Claim(s) <u>5-9 and 12-14</u> is/are rejected. | | | | | | | | |
| 7) Claim(s) is/are objected to. | | | | | | | | |
| 8) Claim(s) are subject to restriction and/or | r election require | ment. | | | | | | |
| Application Papers | | | | | | | | |
| 9)⊠ The specification is objected to by the Examine | r. | | | | | | | |
| 10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner. | | | | | | | | |
| Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). | | | | | | | | |
| 11)☐ The proposed drawing correction filed on is: a)☐ approved b)☐ disapproved by the Examiner. | | | | | | | | |
| If approved, corrected drawings are required in reply to this Office action. | | | | | | | | |
| 12)☐ The oath or declaration is objected to by the Examiner. | | | | | | | | |
| Priority under 35 U.S.C. §§ 119 and 120 | | | | | | | | |
| 13) Acknowledgment is made of a claim for foreigr | priority under 3 | 5 U.S.C. § 119(a | a)-(d) or (f). | | | | | |
| a)⊠ All b)⊡ Some * c)⊡ None of: | | | | | | | | |
| 1. Certified copies of the priority documents have been received. | | | | | | | | |
| 2. Certified copies of the priority documents have been received in Application No | | | | | | | | |
| Copies of the certified copies of the prior application from the International Bu See the attached detailed Office action for a list | reau (PCT Rule : | 17.2(a)). | | l Stage | | | | |
| 14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application). | | | | | | | | |
| a) The translation of the foreign language pro | visional applicati | on has been red | ceived. | | | | | |
| Attachment(s) | o priority under a | 0.0.0. 33 120 | / UIIU/01 12 1. | | | | | |
| 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449) Paper No(s) 3 | 4) | Interview Summar Notice of Informal Other: | y (PTO-413) Paper N Patent Application (P | o(s) TO-152) | | | | |

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DETAILED ACTION

Election/Restrictions

1. Applicant's election without traverse of the invention of group II, claims 5-9 and 12-14 in Paper No. 7 is acknowledged.

Specification

2. The disclosure is objected to because of the following informalities: in line 4 of page 13 "Schottky" is misspelled "Schottkey".

Appropriate correction is required.

3. The title of the invention is not descriptive. A new title is required that is clearly indicative of the invention to which the claims are directed.

Claim Rejections - 35 USC § 112

- 4. The following is a quotation of the second paragraph of 35 U.S.C. 112:

 The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.
- 5. Claims 5-9 and 12-14 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention. The scope of what is being claimed is not clear because, claims 5 and 12 require that the silicidation of surfaces be performed in one step. The specification only teaches performing the silicidation in at least two steps, those steps comprising depositing a metal layer and then reacting the metal layer with the silicon to form the silicide. It is not known if the one step comprises several steps, or the one step is meant to infer that the silicide layer is actually formed in one and only one step.

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Claim Rejections - 35 USC § 102

6. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) do not apply to the examination of this application as the application being examined was not (1) filed on or after November 29, 2000, or (2) voluntarily published under 35 U.S.C. 122(b). Therefore, this application is examined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

7. Claims 5 and 12 are rejected under 35 U.S.C. 102(e) as being anticipated by US patent No. 6,107,154 to Lin.

Lin teaches a method of manufacturing a device having a DRAM and logic section on the same chip, wherein silicidation of the source-drain regions and gates of all transistors is carried out concurrently (Figs. 3A-3F).

Claim Rejections - 35 USC § 103

- 8. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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9. Claims 6-8, 13 and 14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lin.

Regarding claims 6 and 13, Lin teaches a method, wherein the step of silicidation includes forming a metal film over the entire surface of the substrate. Lin does not teach performing a heat treatment to remove the unreacted metal film. It would have been obvious to one of ordinary skill to select the method of using a heat treatment to remove the unreacted metal film as a matter of obvious design choice, since it is only one of many known methods employed to remove unreacted metal from silicide layers.

Regarding claims 7 and 14, Lin teaches a method, wherein the metal film (342) is selected from the group consisting of titanium, cobalt and nickel.

Regarding claim 8, Lin does not teach a method of manufacturing, wherein source/drain implantation is performed at the same time the gates are implanted. The examiner takes official notice that it is common in the art to implant the source/drain region at the same time the gate is implanted. The gate often masks the channel region when the source/drain implant is performed.

10. Claim 9 is rejected under 35 U.S.C. 103(a) as being unpatentable over Lin as applied to claims 5-8 above, and further in view of US patent No. 6,303,432 to Horita et al.

Lin teaches a method, wherein the DRAM includes a bit line (Col. 1, lines 32-34). Lin does not teach forming a bit contact and bit line. It is a matter of obviousness, that in order to have a bit line on the device it must be formed. It would have further been obvious to form a bit line contact to add functionality to the bit line. Lin does not teach

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forming a contact plug to the source/drain region of the logic section. Horita et al. teaches a method of making a DRAM and logic section on the same chip including a step of forming a contact plug (17) to the source/drain region of the logic section. It would have been obvious to one of ordinary skill in the art to incorporated the teaching of Horita et al. into the device taught by Lin, since it is desirable for the logic region of the device to communicate with other elements.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Douglas W Owens whose telephone number is 703-308-6167. The examiner can normally be reached on Monday-Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on 703-308-2772. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-7722 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

TOM THOMAS
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800

DW) January 14, 2002